

In the Claims

Please add new claims 19-39 as follows:

1. (Original) A method of making a transparent article comprising:
providing a transparent, non-metallic substrate; and
depositing upon the substrate, in sequence, a first dielectric film, a metal film, a second dielectric film of a metal oxide, and a protective film of silicon nitride having a thickness in the range of 10 to 150Å.
2. (Original) The method of claim 1 wherein the second dielectric film has an index of refraction essentially the same as that of silicon nitride.
3. (Original) The method of claim 2 wherein said second dielectric film and the silicon nitride film are contiguous.
4. (Original) The method of claim 1 wherein the combined thickness of said second dielectric film and the silicon nitride protective film ranges from about 250 to 400Å.
5. (Original) The method of claim 4 wherein the combined thickness of said second dielectric film and said silicon nitride film is 300-350Å.
6. (Original) The method of claim 5 wherein the combined thickness of said second dielectric film and said silicon nitride film is 275-325Å.
7. (Original) The method of claim 1 wherein the metal film is silver.
8. (Original) The method of claim 7, wherein the metal film of silver is 70 - 100Å.

9. (Original) The method of claim 1 wherein said metal oxide is zinc oxide or titanium dioxide.
10. (Original) The method of claim 1, wherein the metal film is 70 – 100Å.
11. (Original) A method of making a transparent article comprising:
providing a transparent, non-metallic substrate; and
depositing upon the substrate, in sequence, a dielectric film contiguous to the transparent substrate, a metal film, a shielding film contiguous to the metal film, a metal oxide film, and a protective film of from 10Å to 150 Å of silicon nitride contiguous to said metal oxide film.
12. (Original) The method of claim 11 wherein the metal film is silver.
13. (Original) The method of claim 12, wherein the metal film of silver is 70 - 100Å.
14. (Original) The method of claim 11 wherein the index of refraction of the metal oxide film is essentially the same as silicon nitride.
15. (Original) The method of claim 11 wherein the shielding film and the metal oxide film are contiguous.
16. (Original) The method of claim 11 wherein the metal oxide film is zinc oxide or titanium dioxide.
17. (Original) The method of claim 11, wherein the metal film is 70 - 100Å.
18. (Original) The method of claim 11 wherein the combined thickness of said second dielectric film and the silicon nitride protective film ranges from about 250 to 400Å.

19. (New) A transparent article comprising a transparent, non-metallic substrate and a transparent film stack deposited upon the substrate, said film stack comprising, in sequence, an inner dielectric film, a first metal film, a middle dielectric film, a second metal film, an outer dielectric film of metal oxide, and a protective film of silicon nitride having a thickness in the range of 10Å to 100Å.
20. (New) The transparent article of claim 19 wherein the combined thickness of said outer dielectric oxide film and said protective silicon nitride film ranges from about 250Å to 400Å.
21. (New) The transparent article of claim 20 wherein the combined thickness of said outer dielectric oxide film and said protective silicon nitride film is about 275Å to 325Å.
22. (New) The transparent article of claim 19 wherein said outer dielectric oxide film has an index of refraction essentially the same as that of silicon nitride.
23. (New) The transparent article of claim 22 wherein said outer dielectric oxide film is an oxide of zinc, tin, or an alloy thereof.
24. (New) The transparent article of claim 19 wherein said first and second metal films are silver.
25. (New) The transparent article of claim 24 wherein said first metal film has a thickness of 70Å-100Å.
26. (New) The transparent article of claim 19 wherein said protective silicon nitride film has a thickness of 50Å or less.
27. (New) The transparent article of claim 19 wherein said film stack is free of titanium-containing films having a thicknesses greater than about 30Å.

28. (New) The transparent article of claim 19 wherein said inner dielectric film is zinc oxide.
29. (New) A transparent article comprising a transparent, non-metallic substrate and a transparent film stack deposited upon the substrate, said film stack comprising, in sequence, an inner dielectric film, a first metal film, a middle dielectric film, a second metal film, an outer dielectric film of metal oxide, and a protective film of silicon nitride having a thickness in the range of 10 to 100Å, wherein said outer dielectric oxide film and said protective silicon nitride film are contiguous and have a combined thickness in the range of about 250Å to 400Å.
30. (New) The transparent article of claim 29 wherein the combined thickness of said outer dielectric oxide film and said protective silicon nitride film is about 275Å to 325Å.
31. (New) The transparent article of claim 29 wherein said outer dielectric oxide film is zinc oxide or tin oxide.
32. (New) The transparent article of claim 29 wherein said first and second metal films are silver.
33. (New) The transparent article of claim 32 wherein said first metal film has a thickness of 70Å-100Å.
34. (New) A transparent article comprising a transparent, non-metallic substrate and a transparent film stack deposited upon the substrate, said film stack comprising, in sequence, a first film of zinc oxide, a first film of silver, a first shielding film of titanium oxide, a second film of zinc oxide, a second film of silver, a second shielding film of titanium oxide, a third film of zinc oxide, and a protective film of silicon nitride having a thickness in the range of 10 to 100Å.
35. (New) The transparent article of claim 34 wherein said first zinc oxide film has a thickness of in the range of 120-700Å.

36. (New) The transparent article of claim 35 wherein said first zinc oxide film has a thickness of in the range of 300-700Å.
37. (New) The transparent article of claim 34 wherein said first and second shielding films each have a thickness not greater than about 20Å.
38. (New) The transparent article of claim 34 wherein the combined thickness of said third zinc oxide film and said protective silicon nitride film is about 275Å to 325Å.
39. (New) A transparent article comprising a transparent, non-metallic substrate and a transparent film stack deposited upon the substrate, said film stack comprising, in sequence, an inner dielectric film, a first silver film, a middle dielectric film, a second silver film, an outer dielectric film of metal oxide, and a protective film of silicon nitride having a thickness in the range of 10 to 100Å, wherein said outer dielectric oxide film and said protective silicon nitride are contiguous and have a combined thickness in the range of about 250Å to 400Å.